

MBMW-201: The next generation multi-beam mask writer (Conference Presentation) (Withdrawal Notice)

Christof Klein, Hans Loeschner, Elmar Platzgummer

Medizinische Univ. Wien (Austria)

Proc. SPIE 10958, 109580K (2019)

Online Publication Date: 16 August 2019

Withdrawn from Publication: 2 December 2019

Conference Date: 25 February-28 February 2019

Conference Location: San Jose, California, United States

Conference Title: Novel Patterning Technologies for Semiconductors, MEMS/NEMS and MOEMS 2019

Conference Chairs: Martha I. Sanchez

Publisher's Note: This video, originally published on 16 August 2019, was withdrawn per author request.